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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/606,808	06/27/2003	Hae Jin Yun	041501-5583	5874
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MORGAN LEWIS & BOCKIUS LLP			AKKAPEDDI, PRASAD R	
1111 PENNSYLVANIA AVENUE NW WASHINGTON, DC 20004		V	ART UNIT	PAPER NUMBER
	,		2871	

DATE MAILED: 10/28/2004

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)			
	10/606,808	YUN, HAE JIN			
Office Action Summary	Examiner	Art Unit	,		
	Prasad R Akkapeddi	2871	And		
The MAILING DATE of this communication ap Period for Reply	ppears on the cover sheet with the	correspondence add	lress `		
A SHORTENED STATUTORY PERIOD FOR REPL THE MAILING DATE OF THIS COMMUNICATION.  - Extensions of time may be available under the provisions of 37 CFR 1, after SIX (6) MONTHS from the mailing date of this communication.  - If the period for reply specified above is less than thirty (30) days, a repleted in the provided for reply is specified above, the maximum statutory period.  - Failure to reply within the set or extended period for reply will, by stature Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	.136(a). In no event, however, may a reply be timely within the statutory minimum of thirty (30) day I will apply and will expire SIX (6) MONTHS from the cause the application to become ABANDONE.	mely filed  /s will be considered timely. In the mailing date of this continuous (D) (35 U.S.C. § 133).	nmunication.		
Status					
1) Responsive to communication(s) filed on	<u></u> .				
2a) This action is <b>FINAL</b> . 2b) ☑ Thi	s action is non-final.				
3) Since this application is in condition for allows closed in accordance with the practice under			merits is		
Disposition of Claims					
4) ☐ Claim(s) 1-27 is/are pending in the application 4a) Of the above claim(s) is/are withdra 5) ☐ Claim(s) is/are allowed. 6) ☐ Claim(s) 1-27 is/are rejected. 7) ☐ Claim(s) is/are objected to. 8) ☐ Claim(s) are subject to restriction and/	awn from consideration.				
Application Papers					
9)☐ The specification is objected to by the Examin	er.				
0)⊠ The drawing(s) filed on <u>27 June 2003</u> is/are: a)⊠ accepted or b)⊡ objected to by the Examiner.					
Applicant may not request that any objection to the	• • •				
Replacement drawing sheet(s) including the correct 11) The oath or declaration is objected to by the E					
Priority under 35 U.S.C. § 119					
a) Acknowledgment is made of a claim for foreig a) All b) Some * c) None of:  1. Certified copies of the priority document 2. Certified copies of the priority document 3. Copies of the certified copies of the priority document application from the International Bureat*  * See the attached detailed Office action for a list	nts have been received.  Its have been received in Applicatority documents have been received in Applicatority documents have been received.	ion No ed in this National S	Stage		
Attachment(s)	o□	(DTO 442)			
1) Motice of References Cited (PTO-892)  2) Motice of Draftsperson's Patent Drawing Review (PTO-948)	4) Interview Summary Paper No(s)/Mail D				
3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08 Paper No(s)/Mail Date			152)		

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#### **DETAILED ACTION**

### Claim Objections

- 1. Claims 10,11,15, 19 and 21 are objected to because of the following informalities: The following terms have no antecedent basis: 'C-shaped groove' in claim 10; 'the channel region' in claim 11; 'the metal layer' in claim 15; 'the second semiconductor layer, the channel region, the active layer' in claim 19; 'C-shaped groove' in claim 21. Appropriate correction is required.
- 2. Claim 23 is objected to because of the following informalities: The claim language recites "the passivation layer is formed of at least one inorganic insulating layer including silicon nitride or silicon oxide <u>and</u> an organic insulating layer including BenzocycloButene (BCB) or acrylic resin. Whereas, in the specification it is recited that the passivation layer is formed of at least one inorganic insulating layer including silicon nitride or silicon oxide <u>or</u> an organic insulating layer including BenzocycloButene (BCB) or acrylic resin (page 8, lines 15-17). It is not certain whether the passivation layer consists of at least one inorganic layer <u>and/or</u> an organic layer. Appropriate clarification is required.

#### Claim Rejections - 35 USC § 102

3. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

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(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

- 4. Claims 1-22 and 24-27 are rejected under 35 U.S.C. 102(b) as being anticipated by Kim (U.S.Patent No. 5,790,222).
  - a. As to claim 1: Kim discloses a TFT-LCD with an insulating substrate (40), a gate line (42), a first data line (43) perpendicular to the gate line (42) and separated from the gate line by two or more insulating layers (col. 3, lines 8-9), a second data line (49) (upper data line) crossing the gate line (42) on a same line as the first data line (Fig. 4), a thin film transistor (TFT) at the crossing point of the gate line (42) and the second data line (49), an active layer (45, Fig. 5) below the second data line (49), a source electrode (47) and a drain electrode (48), a third data line (49) (lower data line) (col. 2, lines 19-20), disposed perpendicular to the gate line (42) and electrically connects the first and the second data lines with each other (thru contact holes T1 and T2 that can be seen in Fig. 4) and a pixel electrode (51) in the pixel region.
  - b. As to claims 2 and 3: In Fig. 5, Kim discloses that the gate electrode (41) which is an extension of gate line (42) and the data line (43) are on the same layer on top of the substrate and Kim in disclosing the prior art (col. 1, lines 14-15) teaches that the gate electrode is made from chromium.
  - c. As to claim 4: Kim shows in Fig. 5 that the first data line (43) is adjacent to the pixel electrode (51).

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d. As to claim 5: Kim also discloses a passivation layer (50) formed over the entire surface of the insulating layer (44) including the second data line (49) (see Fig. 5).

- e. As to claims 6 and 7: Kim discloses first, second and third contact holes (Fig. 4) on both sides of the first data line (43) and on both sides of the second data line (49) and at the drain electrode (48) and the connection of the data lines through the contact holes is disclosed in (col. 4, lines 33-53).
- f. As to claim 8: Kim discloses that the thin film transistor (TFT) includes a source electrode (47) protruding from the second data line (49), a drain electrode (48) apart from the source electrode (47) and a gate electrode (41) extending from the gate line (42).
- g. As to claims 9 and 10: The partial overlapping of the source electrode (47) and the drain electrode (48) on either side of the gate electrode (41) to define 'C'-shaped groove can be seen from Fig. 4.
- h. As to claim 11: The ohmic contact layer (46) on the active layer (45) corresponding to the second data line (49), the source electrode (47) and the drain electrode (48) except the channel region is shown in Fig. 5
- i. As to claims 12 and 13: Kim discloses a pixel electrode (51) made from ITO (col. 4, lines 50-51) and the location of the pixel electrode with the third data line (49) (lower) is disclosed in (col. 3, lines 40--59).
- j. As to claim 14: The formation of the second data line (49) along with the source electrode (47) and drain electrode (49) via the deposition of an

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amorphous silicon layer (45) and an n+ amorphous silicon layer (46) and a metal layer is disclosed in (col. 3, lines 24-36) and is shown in Fig. 5.

- k. As to claim 15: Kim discloses a method of manufacturing the LCD device (col. 4, lines 8-67 and col. 5, lines 1-42) wherein the method includes a gate line (42), a first data line (43) perpendicular to the gate line (42) and separated from the gate line by two or more insulating layers (col. 3, lines 8-9), a second data line (49) (upper data line) crossing the gate line (42) on a same line as the first data line (Fig. 4), a thin film transistor (TFT) at the crossing point of the gate line (42) and the second data line (49), an active layer (45, Fig. 5) below the second data line (49), a source electrode (47) and a drain electrode (48), a third data line (49) (lower data line) (col. 2, lines 19-20), disposed perpendicular to the gate line (42) and electrically connects the first and the second data lines with each other (thru contact holes T1 and T2 that can be seen in Fig. 4) and a pixel electrode (51) in the pixel region.
- I. As to claims 16 and 17: In Fig. 5, Kim discloses that the gate electrode (41) which is an extension of gate line (42) and the data line (43) are on the same layer on top of the substrate and Kim in disclosing the prior art (col. 1, lines 14-15) teaches that the gate electrode is made from chromium.
- m. As to claim 18: Kim shows in Fig. 5 that the first data line (43) is adjacent to the pixel electrode (51).
- n. As to claim 19: Kim discloses the patterning process by photolithography so that the thin film transistor (TFT) includes a source electrode (47) protruding

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from the second data line (49), a drain electrode (48) apart from the source electrode (47) and a gate electrode (41) extending from the gate line (42). The formation of the second data line (49) along with the source electrode (47) and drain electrode (49) via the deposition of an amorphous silicon layer (45) and an n+ amorphous silicon layer (46) and a metal layer is disclosed in (col. 3, lines 24-36) and is shown in Fig. 5. (col.4, lines 8-46).

- o. As to claims 20 and 21: The partial overlapping of the source electrode (47) and the drain electrode (48) on either side of the gate electrode (41) to define 'C'-shaped groove can be seen from Fig. 4.
- p. As to claim 22: Kim also discloses a passivation layer (50) formed over the entire surface of the insulating layer (44) including the second data line (49) (see Fig. 5).
- q. As to claims 24 and 25: Kim discloses first, second and third contact holes (Fig. 4) on both sides of the first data line (43) and on both sides of the second data line (49) and at the drain electrode (48) and the connection of the data lines through the contact holes is disclosed in (col. 4, lines 33-53).
- r. As to claims 26 and 27: Kim discloses a pixel electrode (51) made from ITO (col. 4, lines 50-51) and the location of the pixel electrode with the third data line (49) (lower) is disclosed in (col. 3, lines 40--59).

## Claim Rejections - 35 USC § 103

5. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

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(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

6. Claim 23 is rejected under 35 U.S.C. 103(a) as being unpatentable over Kim in view of Kim et al. (Kim 2) (U.S.Patent No. 6,100,953).

As to claim 23: Although passivation layers consisting of inorganic and/or organic layers are quite commonly used in liquid crystal displays, and Kim also teaches the use of passivation film (50) on the second data line (49), Kim does not disclose that the passivation film consists of at least one inorganic insulating layer including silicon nitride or silicon oxide and an organic insulating layer including BenzocycloButene (BCB) or acrylic resin.

Kim 2, in disclosing a liquid crystal device teaches that the passivation layer includes BCB, acrylic resin, polyimide compound in addition to silicon nitride or silicon oxide (col. 6, lines 33-34 and 44-46).

Therefore, it would have been obvious to one having ordinary skill in the art at the time the invention was made to adapt the silicon nitride, silicon oxide or the BCB as the material of choice for passivation layer in order to prevent various electrodes from interfering with the distorting electric fields from other electrodes (col. 6,lines 27-31).

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Prasad R Akkapeddi whose telephone number is 571-272-2285. The examiner can normally be reached on 7:00AM to 5:30PM M-Th.

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If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Robert H Kim can be reached on 571-272-2293. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Prasad R Akkapeddi, Ph.D Examiner Art Unit 2871